

## **Silicon Purification - North America**

A North American manufacturer of capital equipment that is used to purify silicon for use in semiconductor wafers sought help on the rate at which a particular transition metal coating would be etched when exposed to the chlorosilane gases at 350 degrees Celsius. Sabol documented all, except one (because of lack of published thermodynamic data), of the gases would not react spontaneously from room temperature to the temperature of interest. Sabol identified a European laboratory that was equipped to expose metal parts to the chlorosilane gases of interest at specified temperatures and verify the predictions.

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